

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-44. (Canceled)

45. (New) An exposure apparatus, comprising:

a movable body that is movable holding a substrate that has been carried from outside;

a liquid supply device that forms a liquid immersion area by supplying liquid on the movable body or the substrate held on the movable body;

an optical member that irradiates the substrate with an exposure light via the liquid in the liquid immersion area, the liquid immersion area being formed between the optical member and the substrate; and

a position setting device that sets a position of the movable body at a predetermined position by moving the movable body using positional information of the movable body, wherein

in a state where the liquid immersion area is formed, the position setting device moves the movable body with first control that uses the positional information, and in a state where the liquid immersion area is not formed, the position setting device moves the movable body using the positional information, with second control that is different from the first control.

46. (New) The exposure apparatus according to claim 45, wherein

the first control is control in which a correction process to correct a positional deviation occurring in at least one of the substrate and the movable body due to supply of the liquid by the liquid supply device is added to the second control.

47. (New) The exposure apparatus according to claim 46, wherein

in the first control, the positional deviation is corrected by changing a value of a thrust given to the movable body using a target value for setting the position of the movable body.

48. (New) The exposure apparatus according to claim 46, wherein
in the first control, the position setting device corrects the positional deviation occurring in at least one of the substrate and the movable body due to supply of the liquid by the liquid supply device, according to a position of the liquid immersion area on the substrate.

49. (New) The exposure apparatus according to claim 48, wherein
the position setting device has a measurement device that measures a position of the movable body or the substrate supported by the movable body, and

in the first control, a positional error occurring in at least one of the substrate and the movable body due to supply of the liquid that is directly or indirectly obtained by the measurement device is corrected.

50. (New) The exposure apparatus according to claim 48, wherein
the position setting device corrects the positional deviation according to a physical quantity related to the liquid supplied by the liquid supply device.

51. (New) The exposure apparatus according to claim 48, wherein
the position setting device has a drive device that drives the movable body, and corrects the positional deviation by changing a thrust of the drive device.

52. (New) The exposure apparatus according to claim 48, further comprising:
a mask stage that holds a mask on which a pattern to be transferred onto the substrate is formed, and that is movable in synchronization with the movable body, wherein
in the first control, the position setting device corrects the positional deviation using a thrust given to at least one of the movable body and the mask stage.

53. (New) The exposure apparatus according to claim 48, wherein

the positional deviation is corrected based on a position measurement result of a transferred image of the pattern that has been transferred onto the substrate.

54. (New) The exposure apparatus according to claim 45, wherein
in the first control, the position setting device moves the movable body by obtaining the positional information in a first calculation process, and in the second control, the position setting device moves the movable body by obtaining the positional information in a second calculation process that is different from the first calculation process.

55. (New) The exposure apparatus according to claim 45, wherein
by the second control, the position setting device moves the movable body from a loading position where the substrate is loaded on the movable body to a supply start position where supply of the liquid is started by the liquid supply device.

56. (New) The exposure apparatus according to claim 55, wherein
the exposure apparatus is a scanning exposure apparatus, and
the position setting device moves the movable body, with the second control, from the loading position to the supply start position, and moves the movable body, with the first control, from the supply start position to a scanning start position where scanning of the movable body for scanning exposure is started.

57. (New) The exposure apparatus according to claim 55, wherein
by the second control, the position setting device moves the movable body from a recovery position used to recover the liquid in the liquid immersion area to an unloading position where the substrate is unloaded from the movable body.

58. (New) An exposure method, comprising:
holding a substrate that has been carried from outside;
forming a liquid immersion area by supplying liquid on the movable body or the substrate held on the movable body;

irradiating the substrate with an exposure light using an optical member via the liquid in the liquid immersion area, the liquid immersion area being formed between the optical member and the substrate; and

setting a position of the movable body at a predetermined position by moving the movable body using positional information of the movable body, wherein

the setting a position of the movable body is performed by moving the movable body with first control that uses the positional information in a state where the liquid immersion area is formed, and by moving the movable body using the positional information with second control that is different from the first control in a state where the liquid immersion area is not formed.

59. (New) The exposure method according to claim 58, wherein

the first control is control in which a correction process to correct a positional deviation occurring in at least one of the substrate and the movable body due to supply of the liquid is added to the second control.

60. (New) The exposure method according to claim 59, wherein

in the first control, the positional deviation is corrected by changing a value of a thrust given to the movable body using a target value for setting the position of the movable body.

61. (New) The exposure method according to claim 59, wherein

in the first control, the positional deviation occurring in at least one of the substrate and the movable body due to supply of the liquid is corrected, according to a position of the liquid immersion area on the substrate.

62. (New) The exposure method according to claim 61, wherein

in the first control, a positional error occurring in at least one of the substrate and the movable body due to supply of the liquid that is directly or indirectly obtained is corrected.

63. (New) The exposure method according to claim 61, wherein
in the first control, the positional deviation is corrected according to a physical quantity related to the supplied liquid.

64. (New) The exposure method according to claim 61, wherein
in the first control, the positional deviation is corrected by changing a thrust given to the movable body.

65. (New) The exposure method according to claim 59, wherein
in the first control, the positional deviation is corrected using a thrust given to at least one of a mask stage that holds a mask on which a pattern to be transferred onto the substrate is formed and that is movable in synchronization with the movable body, and the movable body.

66. (New) The exposure method according to claim 59, wherein
the positional deviation is corrected based on a position measurement result of a transferred image of the pattern that has been transferred onto the substrate.

67. (New) The exposure method according to claim 59, wherein
in the first control, the movable body is moved by obtaining the positional information in a first calculation process, and in the second control, the movable body is moved by obtaining the positional information in a second calculation process that is different from the first calculation process.

68. (New) The exposure method according to claim 59, wherein

by the second control, the movable body is moved from a loading position where the substrate is loaded on the movable body to a supply start position where supply of the liquid is started.

69. (New) The exposure method according to claim 68, wherein the exposure method is a scanning exposure method, and the movable body is moved with the second control from the loading position to the supply start position, and the movable body is moved with the first control from the supply start position to a scanning start position where scanning of the movable body for scanning exposure is started.

70. (New) The exposure method according to claim 68, wherein by the second control, the movable body is moved from a recovery position used to recover the liquid in the liquid immersion area to an unloading position where the substrate is unloaded from the movable body.

71. (New) A device manufacturing method, comprising:
a lithography process in which a device pattern is formed on a substrate with the exposure apparatus according to claim 45.

72. (New) A device manufacturing method, comprising:
a lithography process in which a device pattern is formed on a substrate with the exposure method according to claim 58.